

In re new U.S. patent application of : Attn: Box PCT (DO/EO/US)
Takashi KANDA :
Serial No.: To Be Assigned :
Filed: March 28, 2002 :
For: Aqueous Surfactant Solution for Developing Coating Film Layer

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

Preliminary to the examination of the above-identified application, please amend the application as follows:

In the Claims:

Please amend claims 3, 5, 6, 7, 8, and 9 as follows:

3. (Amended) The surfactant aqueous solution for development of a coating layer according to claim 1, wherein the surfactant is at least one selected from N-lauroylsarcosinate, N-lauroyl-N-methylalaninate, N-lauroyltaurinate, and N-lauroyl-N-methyltaurinate.

5. (Amended) The surfactant aqueous solution for development of a coating layer according to claim 1, wherein the number of carbon atoms of the fatty acid of the fatty acid alkylol amide or the fatty acid alkylol amide polyoxyethylene adduct is 6 to 22, and the number of carbon atoms of the alkylol group thereof is 1 to 3, and the number of repeating units of the polyoxyethylene chain of the fatty acid alkylol amide polyoxyethylene adduct is 10 or less.

6. (Amended) The surfactant aqueous solution for development of a coating layer according to claim 1, wherein the concentration of the surfactant is 0.01 to 10.0

7. (Amended) The surfactant aqueous solution for development of a coating layer according to claim 1, wherein the organic solvent comprises at least one selected from a saturated or unsaturated alcohol with 1 to 8 carbon atoms, a saturated polyvalent alcohol with 2 or 3 hydroxyl groups, a saturated or unsaturated alkyl amine with 1 to 3 carbon atoms, and a saturated or unsaturated alkanol amine with 1 to 3 carbon atoms.

8. (Amended) The surfactant aqueous solution for development of a coating layer according to claim 1, wherein water and the organic solvent are mixed in a ratio of water to the organic solvent of 80:20 to 99:1.

9. (Amended) A method of forming a pattern comprising forming a coating layer on a resist pattern, thickening the resist pattern by crosslinking of the coating layer, and removing the uncrosslinked coating layer with a developer to effectively make the pattern finer, wherein the surfactant aqueous solution for development of a coating layer according to claim 1 is used as a developer.

Version with Markings to Show Changes Made**In the Claims:**

Please amend claims 3, 5, 6, 7, 8, and 9 as follows:

3. (Amended) The surfactant aqueous solution for development of a coating layer according to claim 1 [or 2], wherein the surfactant is at least one selected from N-lauroylsarcosinate, N-lauroyl-N-methylalaninate, N-lauroyltaurinate, and N-lauroyl-N-methyltaurinate.

5. (Amended) The surfactant aqueous solution for development of a coating layer according to claim 1 [or 2], wherein the number of carbon atoms of the fatty acid of the fatty acid alkylol amide or the fatty acid alkylol amide polyoxyethylene adduct is 6 to 22, and the number of carbon atoms of the alkylol group thereof is 1 to 3, and the number of repeating units of the polyoxyethylene chain of the fatty acid alkylol amide polyoxyethylene adduct is 10 or less.

6. (Amended) The surfactant aqueous solution for development of a coating layer according to [any one of] claim[s] 1 [to 5], wherein the concentration of the surfactant is 0.01 to 10.0 % by weight.

7. (Amended) The surfactant aqueous solution for development of a coating layer according to [any one of] claim[s] 1 [to 6], wherein the organic solvent comprises at least one selected from a saturated or unsaturated alcohol with 1 to 8 carbon atoms, a saturated polyvalent alcohol with 2 or 3 hydroxyl groups, a saturated or unsaturated alkyl amine with 1 to 3 carbon atoms, and a saturated or unsaturated alkanol amine with 1 to 3 carbon atoms.

8. (Amended) The surfactant aqueous solution for development of a coating layer according to [any one of] claim[s] 1 [to 7], wherein water and the organic solvent are mixed in a ratio of water to the organic solvent of 80:20 to 99:1.

9. (Amended) A method of forming a pattern comprising forming a coating layer on a resist pattern, thickening the resist pattern by crosslinking of the coating

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CERTIFICATION UNDER 37 CFR 1.10

I hereby certify that on the date indicated above this International application and the documents referred to as enclosed therein, of:

Inventor: Takashi KANDA

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Vicki L. Sgro

